



IFW

Docket No.: 2336-251

PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of :
Seok Taek JUN : Confirmation No.5314
U.S. Patent Application No. 10/791,718 : Group Art Unit: 2814
Filed: March 4, 2004 : Examiner: LONG PHAM
For: TERMINAL STRUCTURE OF MULTI-LAYER SUBSTRATE AND METHOD FOR FORMING
THE SAME

RESPONSE TO RESTRICTION REQUIREMENT

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

By Official Action mailed July 12, 2005 restriction to one of the following inventions is required under 35 USC 121:

- I. Claims 5-9, drawn to a semiconductor process, classified in class 438, subclass 106.
- II. Claims 1-4, drawn to semiconductor device, classified in class 257, subclass 734.

In response, Applicants hereby elect **claims 1-4** for examination in this case.


Early examination on the merits is courteously solicited.

A divisional application will be filed for the non-elected claims.

To the extent necessary, a petition for an extension of time under 37 C.F.R. 1.136 is hereby made. Please charge any shortage in fees due in connection with the filing of this paper, including extension of time fees, to Deposit Account 07-1337 and please credit any excess fees to such deposit account.

Respectfully submitted,

LOWE HAUPTMAN & BERNER, LLP


Randy A. Noranbrock for:
Registration No. 42,940

Benjamin J. Hauptman
Registration No. 29,310

1700 Diagonal Road, Suite 300
Alexandria, Virginia 22314
(703) 684-1111 BJH/tlh
Facsimile: (703) 518-5499
Date: August 11, 2005